

CORRECTED VERSION

(19) World Intellectual Property Organization
International Bureau(43) International Publication Date
27 August 2009 (27.08.2009)

PCT

(10) International Publication Number
WO 2009/105045 A8

(51) International Patent Classification:

B41C 1/10 (2006.01) **H01L 21/02** (2006.01)
B82B 3/00 (2006.01) **B41N 1/14** (2006.01)
G03F 7/00 (2006.01) **C09D 11/10** (2006.01)
B41C 1/06 (2006.01) **H01L 51/40** (2006.01)
C09D 11/02 (2006.01)

Crescent, #07-05, Singapore 637819 (SG).
MHAISALKAR, Subodh, Gautam [SG/SG]; 9 Sin
 Ming Walk, #18-01, Singapore 575578 (SG).

(74) Agent: **CALLINAN, Keith, William**; Marks & Clerk
 Singapore LLP, Tanjong Pagar, P.O. Box 636, Singapore
 910816 (SG).

(21) International Application Number:

PCT/SG2009/000064

(81) Designated States (unless otherwise indicated, for every
 kind of national protection available): AE, AG, AL, AM,
 AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ,
 CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ,
 EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN,
 HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR,
 KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME,
 MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO,
 NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG,
 SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA,
 UG, US, UZ, VC, VN, ZA, ZM, ZW.

(22) International Filing Date:

23 February 2009 (23.02.2009)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

61/030,762 22 February 2008 (22.02.2008) US

(71) Applicant (for all designated States except US):

NANYANG TECHNOLOGICAL UNIVERSITY [SG/
 SG]; 50 Nanyang Avenue, Singapore 639798 (SG).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **BHUPENDRA,
 Kumar** [IN/US]; 8950 Costa Verde Blvd, Apt 4109, San
 Diego, CA 92122 (US). **ZHANG, Yuanyuan** [CN/SG]; c/
 o Nanyang Technological University, 50 Nanyang Ave-
 nue, Singapore 639798 (SG). **WANG, Zongbin**
 [CN/SG]; Blk 85C, Toa Payoh Lorong 4, #08-372, Singa-
 pore 313085 (SG). **LI, Lain-Jong** [—/SG]; 100 Nanyang

(84) Designated States (unless otherwise indicated, for every
 kind of regional protection available): ARIPO (BW, GH,
 GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM,
 ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ,
 TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE,
 ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV,
 MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR),
 OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML,
 MR, NE, SN, TD, TG).

Declarations under Rule 4.17:

[Continued on next page]

(54) Title: PATTERNING OF NANOSTRUCTURES

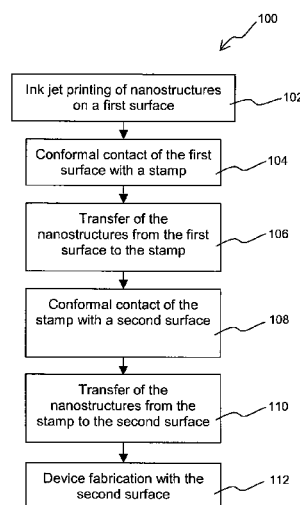


FIG. 1A

(57) Abstract: A method of patterning nanostructures comprising printing an ink comprising the nanostructures onto a solvent-extracting first surface such that a pattern of nanostructures is formed on the first surface.



— *of inventorship (Rule 4.17(iv))*

(48) Date of publication of this corrected version:

22 October 2009

Published:

— *with international search report (Art. 21(3))*

(15) Information about Correction:

see Notice of 22 October 2009